L Number	Hits	Search Text	DB	Time stamp
-	363	("so.sub.2" so2 (sulph?r sulfur) adj	USPAT;	2003/12/19 02:14
		\$20xide) and ("CF.sub.4" CF4 "NF.sub.3" NF3	EPO; JPO;	
		"SF.sub.6" SF6 (carbon nitrogen sulfur) adj	DERWENT;	
	100	\$4fluoride) and (argon ar)   (("so.sub.2" so2 (sulph?r sulfur) adj	IBM_TDB USPAT;	2001/03/05 14:56
-	102	\$20xide) and ("CF.sub.4" CF4 "NF.sub.3" NF3	EPO; JPO;	2001/03/03 14.30
		"SF.sub.6" SF6 (carbon nitrogen sulfur) adj	DERWENT;	
		\$4fluoride) and (argon ar)) and plasma and	IBM TDB	
		etch\$3	_	
-	55		USPAT;	2001/03/05 15:19
		\$20xide) and ("CF.sub.4" CF4 "NF.sub.3" NF3	EPO; JPO;	
		"SF. sub.6" SF6 (carbon nitrogen sulfur) adj	DERWENT;	
		\$4fluoride) and (argon ar)) and (("so.sub.2" so2 (sulph?r sulfur) adj \$2oxide) same	IBM_TDB	
		("CF.sub.4" CF4 "NF.sub.3" NF3 "SF.sub.6"		
		SF6 (carbon nitrogen sulfur) adj \$4fluoride)		
		same (argon ar))		
-	16	((("so.sub.2" so2 (sulph?r sulfur) adj	USPAT;	2001/03/05 15:20
]		\$20xide) and ("CF.sub.4" CF4 "NF.sub.3" NF3	EPO; JPO;	
		"SF.sub.6" SF6 (carbon nitrogen sulfur) adj	DERWENT;	
		\$4fluoride) and (argon ar)) and (("so.sub.2"	IBM_TDB	
		so2 (sulph?r sulfur) adj \$20xide) same ("CF.sub.4" CF4 "NF.sub.3" NF3 "SF.sub.6"		
		SF6 (carbon nitrogen sulfur) adj \$4fluoride)		
'		same (argon ar))) and plasma and etch\$3		
-	0	((("so.sub.2" so2 (sulph?r sulfur) adj	USPAT;	2001/03/05 15:17
		\$20xide) and ("CF.sub.4" CF4 "NF.sub.3" NF3	EPO; JPO;	
		"SF.sub.6" SF6 (carbon nitrogen sulfur) adj	DERWENT;	
		\$4fluoride) and (argon ar)) and (("so.sub.2"	IBM_TDB	
		so2 (sulph?r sulfur) adj \$20xide) same ("CF.sub.4" CF4 "NF.sub.3" NF3 "SF.sub.6"		
		SF6 (carbon nitrogen sulfur) adj \$4fluoride)		
		same (argon ar))) and etch\$3 not		
		(((("so.sub.2" so2 (sulph?r sulfur) adj		
		\$20xide) and ("CF.sub.4" CF4 "NF.sub.3" NF3		
†		"SF. sub.6" SF6 (carbon nitrogen sulfur) adj		
		\$4fluoride) and (argon ar)) and (("so.sub.2"		
		so2 (sulph?r sulfur) adj \$20xide) same ("CF.sub.4" CF4 "NF.sub.3" NF3 "SF.sub.6"		
		SF6 (carbon nitrogen sulfur) adj \$4fluoride)		
		same (argon ar))) and plasma and etch\$3)		
-	4	((("so.sub.2" so2 (sulph?r sulfur) adj	USPAT;	2001/03/06 13:29
		\$20xide) and ("CF.sub.4" CF4 "NF.sub.3" NF3	EPO; JPO;	
		"SF. sub.6" SF6 (carbon nitrogen sulfur) adj	DERWENT;	
		\$4fluoride) and (argon ar)) and (("so.sub.2"	IBM_TDB	
		so2 (sulph?r sulfur) adj \$20xide) same ("CF.sub.4" CF4 "NF.sub.3" NF3 "SF.sub.6"		
		SF6 (carbon nitrogen sulfur) adj \$4fluoride)		
		same (argon ar))) and plasma not		
		(((("so.sub.2" so2 (sulph?r sulfur) adj		
		\$20xide) and ("CF.sub.4" CF4 "NF.sub.3" NF3		
		"SF.sub.6" SF6 (carbon nitrogen sulfur) adj		
		\$4fluoride) and (argon ar)) and (("so.sub.2"		
		so2 (sulph?r sulfur) adj \$20xide) same		
		("CF.sub.4" CF4 "NF.sub.3" NF3 "SF.sub.6" SF6 (carbon nitrogen sulfur) adj \$4fluoride)		
		same (argon ar))) and plasma and etch\$3)		
-	124		USPAT;	2001/03/05 15:21
		\$20xide) and ("CF.sub.4" CF4 "NF.sub.3" NF3	EPO; JPO;	
		"SF.sub.6" SF6 (carbon nitrogen sulfur) adj	DERWENT;	
		\$4fluoride) and (argon ar)) and (argon ar)	IBM_TDB	
		and (("so.sub.2" so2 (sulph?r sulfur) adj		
		\$20xide) same ("CF.sub.4" CF4 "NF.sub.3" NF3		
		<pre>"SF.sub.6" SF6 (carbon nitrogen sulfur) adj \$4fluoride))</pre>		
L		SALTHOLINE)	1	1

			100 / 100 / 100 / 100
- 20	((("so.sub.2" so2 (sulph?r sulfur) adj	USPAT;	2001/03/05 15:53
	\$20xide) and ("CF.sub.4" CF4 "NF.sub.3" NF3	EPO; JPO;	
	"SF.sub.6" SF6 (carbon nitrogen sulfur) adj	DERWENT;	
	\$4fluoride) and (argon ar)) and (argon ar)	IBM_TDB	
	and (("so.sub.2" so2 (sulph?r sulfur) adj		
	\$20xide) same ("CF.sub.4" CF4 "NF.sub.3" NF3		
	"SF.sub.6" SF6 (carbon nitrogen sulfur) adj		
	\$4fluoride))) and plasma and etch\$3 not		
	((((("so.sub.2" so2 (sulph?r sulfur) adj		
	\$2oxide) and ("CF.sub.4" CF4 "NF.sub.3" NF3		
	"SF.sub.6" SF6 (carbon nitrogen sulfur) adj		
	\$4fluoride) and (argon ar)) and (("so.sub.2"	ļ	
	so2 (sulph?r sulfur) adj \$20xide) same		
i i	("CF.sub.4" CF4 "NF.sub.3" NF3 "SF.sub.6"	ĺ	
	SF6 (carbon nitrogen sulfur) adj \$4fluoride)		
į	same (argon ar))) and plasma and etch\$3)		
	(((("so.sub.2" so2 (sulph?r sulfur) adj		
	\$20xide) and ("CF.sub.4" CF4 "NF.sub.3" NF3		
	"SF.sub.6" SF6 (carbon nitrogen sulfur) adj		
	\$4fluoride) and (argon ar)) and (("so.sub.2"		
	so2 (sulph?r sulfur) adj \$20xide) same		
	("CF.sub.4" CF4 "NF.sub.3" NF3 "SF.sub.6"		
	SF6 (carbon nitrogen sulfur) adj \$4fluoride)		
	same (argon ar))) and plasma not		
	(((("so.sub.2" so2 (sulph?r sulfur) adj		
	\$20xide) and ("CF.sub.4" CF4 "NF.sub.3" NF3		
	"SF.sub.6" SF6 (carbon nitrogen sulfur) adj		
	\$4fluoride) and (argon ar)) and (("so.sub.2"		
	so2 (sulph?r sulfur) adj \$20xide) same	,	
1	("CF.sub.4" CF4 "NF.sub.3" NF3 "SF.sub.6"		
	SF6 (carbon nitrogen sulfur) adj \$4fluoride)		
	same (argon ar))) and plasma and etch\$3)))		

2001/03/05 15:53 USPAT; ((("so.sub.2" so2 (sulph?r sulfur) adj \$20xide) and ("CF.sub.4" CF4 "NF.sub.3" NF3 EPO; JPO; "SF.sub.6" SF6 (carbon nitrogen sulfur) adj DERWENT; IBM\_TDB \$4fluoride) and (argon ar)) and (argon ar) and (("so.sub.2" so2 (sulph?r sulfur) adj \$20xide) same ("CF.sub.4" CF4 "NF.sub.3" NF3 "SF.sub.6" SF6 (carbon nitrogen sulfur) adj \$4fluoride))) and etch\$3 not ((((("so.sub.2" so2 (sulph?r sulfur) adj \$20xide) and ("CF.sub.4" CF4 "NF.sub.3" NF3 "SF.sub.6" SF6 (carbon nitrogen sulfur) adj \$4fluoride) and (argon ar)) and (("so.sub.2" so2 (sulph?r sulfur) adj \$20xide) same ("CF.sub.4" CF4 "NF.sub.3" NF3 "SF.sub.6" SF6 (carbon nitrogen sulfur) adj \$4fluoride) same (argon ar))) and plasma and etch\$3) (((("so.sub.2" so2 (sulph?r sulfur) adj \$20xide) and ("CF.sub.4" CF4 "NF.sub.3" NF3 "SF.sub.6" SF6 (carbon nitrogen sulfur) adj \$4fluoride) and (argon ar)) and (("so.sub.2" so2 (sulph?r sulfur) adj \$20xide) same ("CF.sub.4" CF4 "NF.sub.3" NF3 "SF.sub.6" SF6 (carbon nitrogen sulfur) adj \$4fluoride) same (argon ar))) and plasma not (((("so.sub.2" so2 (sulph?r sulfur) adj \$20xide) and ("CF.sub.4" CF4 "NF.sub.3" NF3 "SF.sub.6" SF6 (carbon nitrogen sulfur) adj \$4fluoride) and (argon ar)) and (("so.sub.2" so2 (sulph?r sulfur) adj \$20xide) same ("CF.sub.4" CF4 "NF.sub.3" NF3 "SF.sub.6" SF6 (carbon nitrogen sulfur) adj \$4fluoride) same (argon ar))) and plasma and etch\$3)) (((("so.sub.2" so2 (sulph?r sulfur) adj \$20xide) and ("CF.sub.4" CF4 "NF.sub.3" NF3 "SF.sub.6" SF6 (carbon nitrogen sulfur) adj \$4fluoride) and (argon ar)) and (argon ar) and (("so.sub.2" so2 (sulph?r sulfur) adj \$2oxide) same ("CF.sub.4" CF4 "NF.sub.3" NF3 "SF.sub.6" SF6 (carbon nitrogen sulfur) adj \$4fluoride))) and plasma and etch\$3 not ((((("so.sub.2" so2 (sulph?r sulfur) adj \$2oxide) and ("CF.sub.4" CF4 "NF.sub.3" NF3 "SF.sub.6" SF6 (carbon nitrogen sulfur) adj \$4fluoride) and (argon ar)) and (("so.sub.2" so2 (sulph?r sulfur) adj \$20xide) same ("CF.sub.4" CF4 "NF.sub.3" NF3 "SF.sub.6" SF6 (carbon nitrogen sulfur) adj \$4fluoride) same (argon ar))) and plasma and etch\$3) (((("so.sub.2" so2 (sulph?r sulfur) adj \$20xide) and ("CF.sub.4" CF4 "NF.sub.3" NF3 "SF.sub.6" SF6 (carbon nitrogen sulfur) adj \$4fluoride) and (argon ar)) and (("so.sub.2" so2 (sulph?r sulfur) adj \$20xide) same ("CF.sub.4" CF4 "NF.sub.3" NF3 "SF.sub.6" SF6 (carbon nitrogen sulfur) adj \$4fluoride) same (argon ar))) and plasma not (((("so.sub.2" so2 (sulph?r sulfur) adj \$20xide) and ("CF.sub.4" CF4 "NF.sub.3" NF3 "SF.sub.6" SF6 (carbon nitrogen sulfur) adj \$4fluoride) and (argon ar)) and (("so.sub.2" so2 (sulph?r sulfur) adj \$20xide) same ("CF.sub.4" CF4 "NF.sub.3" NF3 "SF.sub.6" SF6 (carbon nitrogen sulfur) adj \$4fluoride) same (argon ar))) and plasma and etch\$3)))))

-	16	((("so.sub.2" so2 (sulph?r sulfur) adj	USPAT;	2001/03/05 15:54
		\$20xide) and ("CF.sub.4" CF4 "NF.sub.3" NF3	EPO; JPO;	
		"SF.sub.6" SF6 (carbon nitrogen sulfur) adj	DERWENT;	
		\$4fluoride) and (argon ar)) and (argon ar)	IBM_TDB	
		and (("so.sub.2" so2 (sulph?r sulfur) adj	_	
		\$20xide) same ("CF.sub.4" CF4 "NF.sub.3" NF3		
		"SF.sub.6" SF6 (carbon nitrogen sulfur) adj		
		\$4fluoride))) and plasma not (((("so.sub.2"		
		so2 (sulph?r sulfur) adj \$20xide) and		
		("CF.sub.4" CF4 "NF.sub.3" NF3 "SF.sub.6"		
		SF6 (carbon nitrogen sulfur) adj \$4fluoride)		
		and (argon ar)) and (("so.sub.2" so2		
		(sulph?r sulfur) adj \$20xide) same	i	
		("CF.sub.4" CF4 "NF.sub.3" NF3 "SF.sub.6"		
		SF6 (carbon nitrogen sulfur) adj \$4fluoride)		
		same (argon ar))) and plasma and etch\$3)	l.	
		(((("so.sub.2" so2 (sulph?r sulfur) adj		
		\$20xide) and ("CF.sub.4" CF4 "NF.sub.3" NF3		
		"SF.sub.6" SF6 (carbon nitrogen sulfur) adj		
		\$4fluoride) and (argon ar)) and (("so.sub.2"		
		so2 (sulph?r sulfur) adj \$2oxide) same		
		("CF.sub.4" CF4 "NF.sub.3" NF3 "SF.sub.6"		
		SF6 (carbon nitrogen sulfur) adj \$4fluoride)		
		same (argon ar))) and plasma not		
		(((("so.sub.2" so2 (sulph?r sulfur) adj		
		\$20xide) and ("CF.sub.4" CF4 "NF.sub.3" NF3		
,		"SF.sub.6" SF6 (carbon nitrogen sulfur) adj		
		\$4fluoride) and (argon ar)) and (("so.sub.2"		
•		so2 (sulph?r sulfur) adj \$20xide) same		
ı		("CF.sub.4" CF4 "NF.sub.3" NF3 "SF.sub.6"		
		SF6 (carbon nitrogen sulfur) adj \$4fluoride)		
		same (argon ar))) and plasma and etch\$3))		
		(((("so.sub.2" so2 (sulph?r sulfur) adj		
		\$20xide) and ("CF.sub.4" CF4 "NF.sub.3" NF3		
		"SF.sub.6" SF6 (carbon nitrogen sulfur) adj		
!		\$4fluoride) and (argon ar)) and (argon ar)		·
		and (("so.sub.2" so2 (sulph?r sulfur) adj		Į.
		\$20xide) same ("CF.sub.4" CF4 "NF.sub.3" NF3		
		"SF.sub.6" SF6 (carbon nitrogen sulfur) adj		
		\$4fluoride))) and plasma and etch\$3 not		
		((((("so.sub.2" so2 (sulph?r sulfur) adj		
		\$20xide) and ("CF.sub.4" CF4 "NF.sub.3" NF3		
		"SF.sub.6" SF6 (carbon nitrogen sulfur) adj		
		\$4fluoride) and (argon ar)) and (("so.sub.2"		
		so2 (sulph?r sulfur) adj \$20xide) same		
İ		("CF.sub.4" CF4 "NF.sub.3" NF3 "SF.sub.6"		
		SF6 (carbon nitrogen sulfur) adj \$4fluoride)		
		same (argon ar))) and plasma and etch\$3)		
		(((("so.sub.2" so2 (sulph?r sulfur) adj		
	ļ	\$20xide) and ("CF.sub.4" CF4 "NF.sub.3" NF3		
		"SF.sub.6" SF6 (carbon nitrogen sulfur) adj	Į	
		\$4fluoride) and (argon ar)) and (("so.sub.2"		
		so2 (sulph?r sulfur) adj \$2oxide) same		
		("CF.sub.4" CF4 "NF.sub.3" NF3 "SF.sub.6"		
		SF6 (carbon nitrogen sulfur) adj \$4fluoride)		
		same (argon ar))) and plasma not		ł
1		(((("so.sub.2" so2 (sulph?r sulfur) adj		1
i		\$20xide) and ("CF.sub.4" CF4 "NF.sub.3" NF3		
	<b>!</b>	"SF.sub.6" SF6 (carbon nitrogen sulfur) adj		
		\$4fluoride) and (argon ar)) and (("so.sub.2"	I	
	1	so2 (sulph?r sulfur) adj \$20xide) same		•
		("CF.sub.4" CF4 "NF.sub.3" NF3 "SF.sub.6"		
		SF6 (carbon nitrogen sulfur) adj \$4fluoride)		
		same (argon ar))) and plasma and etch\$3)))))	1	
l _	24	l	USPAT;	2003/12/18 15:49
	24	US-4793897-\$.DID. OR US-5211790-\$.DID. OR	US-PGPUB;	
		US-5362361-\$.DID. OR US-5397431-\$.DID. OR	EPO; JPO;	
	1	US-5721090-\$.DID. OR US-5753418-\$.DID. OR	DERWENT;	
	1	US-5779926-\$.DID. OR US-5817579-\$.DID. OR	IBM TDB	
		עדרי ל-ב//ביב/ ארי עדרי ל-בסר ארי ל-בסידער ל-פרי ו	1 100 100	1
		US-5910392-\$.DID. OR US-5911887-\$.DID.	i –	İ

-	15	US-Re30505-\$.DID. OR US-4615764-\$.DID. OR	USPAT	2003/12/18 15:49
,		US-4793897-\$.DID. OR US-5211790-\$.DID. OR		
		US-5362361-\$.DID. OR US-5397431-\$.DID. OR		
		US-5721090-\$.DID. OR US-5753418-\$.DID. OR US-5779926-\$.DID. OR US-5817579-\$.DID. OR		_
·		US-5910392-\$.DID. OR US-5911887-\$.DID. OR		-
1		US-6080678-\$.DID. OR US-6110826-\$.DID. OR		
		US-6132631-\$.DID.		
_	30		USPAT;	2003/12/18 15:51
		US-4793897-\$.DID. OR US-5211790-\$.DID. OR	US-PGPUB;	
		US-5362361-\$.DID. OR US-5397431-\$.DID. OR	EPO; JPO;	
		US-5721090-\$.DID. OR US-5753418-\$.DID. OR	DERWENT;	
		US-5779926-\$.DID. OR US-5817579-\$.DID. OR US-5910392-\$.DID. OR US-5911887-\$.DID. OR	IBM_TDB	
		US-6080678-\$.DID. OR US-6110826-\$.DID. OR		
		US-6132631-\$.DID.		
_	ا ه	· · · · · · · · · · · · · · · · · · ·	USPAT;	2003/12/18 15:51
			US-PGPUB;	
,			EPO; JPO;	
			DERWENT;	
			IBM_TDB	2002/12/10 15 52
-	3	"9616437"	USPAT; US-PGPUB;	2003/12/18 15:52
			EPO; JPO;	
			DERWENT;	•
			IBM TDB	
_	33	(US-Re30505-\$.DID. OR US-4615764-\$.DID. OR	USPAT;	2003/12/18 15:59
1.		US-4793897-\$.DID. OR US-5211790-\$.DID. OR	US-PGPUB;	
		US-5362361-\$.DID. OR US-5397431-\$.DID. OR	EPO; JPO;	
		US-5721090-\$.DID. OR US-5753418-\$.DID. OR	DERWENT;	
		US-5779926-\$.DID. OR US-5817579-\$.DID. OR	IBM_TDB	
		US-5910392-\$.DID. OR US-5911887-\$.DID. OR US-6080678-\$.DID. OR US-6110826-\$.DID. OR		
	1	US-6132631-\$.DID. OR US-6110026-\$.DID. OR		
_	15		USPAT;	2003/12/18 16:37
		N.sub.4") and (("so.sub.2" so2 (sulph?r	US-PGPUB;	
		sulfur) adj \$20xide) same (fluoride fluorine	EPO; JPO;	
		"CF.sub.4" CF4 "NF.sub.3" NF3 "SF.sub.6"	DERWENT;	
	_	SF6))	IBM_TDB USPAT	2003/12/18 16:13
-	0	20020003126.URPN. 20020003126.URPN.	USPAT	2003/12/18 16:13
1_	1	2002-178961.NRAN.	DERWENT	2003/12/18 16:13
1-	33	l	USPAT;	2003/12/18 16:17
		US-4793897-\$.DID. OR US-5211790-\$.DID. OR	US-PGPUB;	
		US-5362361-\$.DID. OR US-5397431-\$.DID. OR	EPO; JPO;	
		US-5721090-\$.DID. OR US-5753418-\$.DID. OR	DERWENT;	
1.	1	US-5779926-\$.DID. OR US-5817579-\$.DID. OR	IBM_TDB	
	1	US-5910392-\$.DID. OR US-5911887-\$.DID. OR US-6080678-\$.DID. OR US-6110826-\$.DID. OR		
	1	US-6132631-\$.DID.) "9616437") not (etch\$3		
	1	and DUV and (nitride Si3N4 "Si.sub.3		
	1	N.sub.4") and (("so.sub.2" so2 (sulph?r		
	1	sulfur) adj \$20xide) same (fluoride fluorine		
	1	"CF.sub.4" CF4 "NF.sub.3" NF3 "SF.sub.6"		
		SF6)))	USPAT;	2003/12/18 16:38
-	99	etch\$3 and (photoresist resist DUV) and (nitride Si3N4 "Si.sub.3 N.sub.4") and	US-PGPUB;	2003, 12, 10 10.30
		(("so.sub.2" so2 (sulph?r sulfur) adj	EPO; JPO;	
		\$20xide) same (fluoride fluorine "CF.sub.4"	DERWENT;	
		CF4 "NF.sub.3" NF3 "SF.sub.6" SF6))	IBM_TDB	
-	119	etch\$3 and (organic photoresist resist DUV)	USPAT;	2003/12/18 16:39
		and (nitride Si3N4 "Si.sub.3 N.sub.4") and	US-PGPUB;	
	1	(("so.sub.2" so2 (sulph?r sulfur) adj	EPO; JPO;	
	1	\$20xide) same (fluoride fluorine "CF.sub.4" CF4 "NF.sub.3" NF3 "SF.sub.6" SF6))	DERWENT; IBM TDB	
_	21		USPAT;	2003/12/18 16:40
		and (nitride Si3N4 "Si.sub.3 N.sub.4") and	US-PGPUB;	, , , == ==
		(("so.sub.2" so2 (sulph?r sulfur) adj	EPO; JPO;	
		\$20xide) same (fluoride fluorine "CF.sub.4"	DERWENT;	
		CF4 "NF.sub.3" NF3 "SF.sub.6" SF6))) and	IBM_TDB	
		selecti\$5 same (organic photoresist resist		
		DUV) same (nitride Si3N4 "Si.sub.3 N.sub.4")	L	<u> </u>

-	4	(("RE30505") or ("5211790") or ("5753418") or ("5817579")).PN.	USPAT	2003/12/19 01:27
_	0	• • •	USPAT	2003/12/19 02:05
_	- 1	2002-178961.NRAN.	DERWENT	2003/12/19 02:05
	6		USPAT;	2003/12/19 02:22
		adj \$20xide) same ("SF.sub.6" SF6 (sulph?r	EPO; JPO;	
		sulfur) adj \$4fluoride) and (HBr hydrogen	DERWENT;	
		adj bromide)	IBM TDB	
_	5	l	USPAT;	2003/12/19 02:21
		N.sub.4" DUV resist photoresist) and	EPO; JPO;	
		("SO.sub.2" SO2 (sulph?r sulfur) adj	DERWENT;	
		\$20xide) same ("SF.sub.6" SF6 (sulph?r	IBM_TDB	1
		sulfur) adj \$4fluoride) and (HBr hydrogen	_	
	+	adj bromide)		
-	2	etch\$3 same (nitride SiN Si3N4 "Si.sub.3	USPAT;	2003/12/19 02:21
		N.sub.4" DUV resist photoresist) and	EPO; JPO;	i
		("SO.sub.2" SO2 (sulph?r sulfur) adj	DERWENT;	
		\$20xide) same ("SF.sub.6" SF6 (sulph?r	IBM_TDB	
		sulfur) adj \$4fluoride) same (HBr hydrogen		
	1	adj bromide)		
-	29	etch\$3 same (nitride SiN Si3N4 "Si.sub.3	USPAT;	2003/12/19 02:22
		N.sub.4" DUV resist photoresist) and	EPO; JPO;	,
		("SO.sub.2" SO2 (sulph?r sulfur) adj	DERWENT;	
		\$2oxide) same ("SF.sub.6" SF6 (sulph?r	IBM_TDB	
	·	sulfur) adj \$4fluoride)		
-	60		USPAT;	2003/12/19 02:22
		adj \$2oxide) same ("SF.sub.6" SF6 (sulph?r	EPO; JPO;	
		sulfur) adj \$4fluoride)	DERWENT;	
			IBM_TDB	
-	24		USPAT;	2003/12/19 02:33
		US-6080678-\$ or US-6110826-\$ or US-5910392-\$	US-PGPUB	
		or US-5362361-\$ or US-5721090-\$ or		
		US-5397431-\$ or US-5779926-\$ or US-4615764-\$		
		or US-4793897-\$ or US-5877075-\$ or		
		US-6015597-\$ or US-6617257-\$ or US-6261905-\$		
		or US-6204168-\$ or US-5824604-\$ or		
		US-5798562-\$ or US-5445712-\$ or US-4431477-\$		
		or US-6225220-\$ or US-6149828-\$).did. or		
	1 10	(US-20010005623-\$ or US-20020076935-\$).did.	USPAT	2003/12/19 02:53
-	18	(etch\$3 same (nitride SiN Si3N4 "Si.sub.3	USFAI	2003/12/13 02:53
,		N.sub.4" DUV resist photoresist) and ("SO.sub.2" SO2 (sulph?r sulfur) adj		
	1	\$20xide) same ("SF.sub.6" SF6 (sulph?r		
		sulfur) adj \$4fluoride)) not ((etch\$3 and		
		("SO.sub.2" SO2 (sulph?r sulfur) adj		
		\$20xide) same ("SF.sub.6" SF6 (sulph?r		
		sulfur) adj \$4fluoride) and (HBr hydrogen		
		adj bromide)) ((US-6132631-\$ or US-5911887-\$		
		or US-6080678-\$ or US-6110826-\$ or		
		US-5910392-\$ or US-5362361-\$ or US-5721090-\$		
		or US-5397431-\$ or US-5779926-\$ or		
		US-4615764-\$ or US-4793897-\$ or US-5877075-\$	1	
		or US-6015597-\$ or US-6617257-\$ or		
		US-6261905-\$ or US-6204168-\$ or US-5824604-\$		
		or US-5798562-\$ or US-5445712-\$ or		
		US-4431477-\$ or US-6225220-\$ or		
l		US-6149828-\$).did. or (US-20010005623-\$ or	1	1
		00 0115020 07.010. 01 (00 0001000000 7 01	1	

- 26 (etch\$3 and ("SO.sub.2" SO2 (sulph?r sulfur) adj \$20xide) same ("SF.sub.6" SF6 (sulph?r sulfur) adj \$4fluoride)) not ((etch\$3 same (nitride SiN Si3N4 "Si.sub.3 N.sub.4" DUV resist photoresist) and ("SO.sub.2" SO2 (sulph?r sulfur) adj \$20xide) same ("SF.sub.6" SF6 (sulph?r sulfur) adj \$4fluoride)) (etch\$3 and ("SO.sub.2" SO2	2003/12/19 02:53
sulfur) adj \$4fluoride)) not ((etch\$3 same (nitride SiN Si3N4 "Si.sub.3 N.sub.4" DUV resist photoresist) and ("SO.sub.2" SO2 (sulph?r sulfur) adj \$20xide) same ("SF.sub.6" SF6 (sulph?r sulfur) adj	
(nitride SiN Si3N4 "Si.sub.3 N.sub.4" DUV resist photoresist) and ("SO.sub.2" SO2 (sulph?r sulfur) adj \$20xide) same ("SF.sub.6" SF6 (sulph?r sulfur) adj	
resist photoresist) and ("SO.sub.2" SO2 (sulph?r sulfur) adj \$20xide) same ("SF.sub.6" SF6 (sulph?r sulfur) adj	
(sulph?r sulfur) adj \$20xide) same ("SF.sub.6" SF6 (sulph?r sulfur) adj	
("SF.sub.6" SF6 (sulph?r sulfur) adj	
i i Sarinoride)) (erchS3 and USO.SND.Z" SOZ i	
(sulph?r sulfur) adj \$20xide) same	
("SF.sub.6" SF6 (sulph?r sulfur) adj	
\$4fluoride) and (HBr hydrogen adj bromide))	
((US-6132631-\$ or US-5911887-\$ or	
US-6080678-\$ or US-6110826-\$ or US-5910392-\$	
or US-5362361-\$ or US-5721090-\$ or	
US-5397431-\$ or US-5779926-\$ or US-4615764-\$	
or US-4793897-\$ or US-5877075-\$ or	
US-6015597-\$ or US-6617257-\$ or US-6261905-\$	
or US-6204168-\$ or US-5824604-\$ or	
US-5798562-\$ or US-5445712-\$ or US-4431477-\$	
or US-6225220-\$ or US-6149828-\$).did. or	
(US-20010005623-\$ or	
US-20020076935-\$).did.))	
- 26 (US-5877075-\$ or US-6149828-\$ or USPAT;	2003/12/29 11:59
US-6015597-\$ or US-6110826-\$ or US-6132631-\$ US-PGPUB	2003/12/23 11:33
or US-6080678-\$ or US-5911887-\$ or	
US-5910392-\$ or US-5779926-\$ or US-5721090-\$	
or US-5397431-\$ or US-5362361-\$ or	
US-4793897-\$ or US-4615764-\$ or US-6444559-\$	
or US-6617257-\$ or US-6261905-\$ or	1
US-6204168-\$ or US-5824604-\$ or US-5798562-\$	1
or US-5445712-\$ or US-4431477-\$ or	
US-6225220-\$ or US-5114827-\$).did. or	
(US-20010005623-\$ or US-20020076935-\$).did.	
- 5 ((US-5877075-\$ or US-6149828-\$ or USPAT;	2003/12/29 12:09
US-6015597-\$ or US-6110826-\$ or US-6132631-\$ US-PGPUB	, · · · · · · · · · · · · · · · · · · ·
or US-6080678-\$ or US-5911887-\$ or EPO; JPO	
US-5910392-\$ or US-5779926-\$ or US-5721090-\$ DERWENT;	<b>'</b>
or US-5397431-\$ or US-5362361-\$ or IBM TDB	
US-4793897-\$ or US-4615764-\$ or US-6444559-\$	
or US-6617257-\$ or US-6261905-\$ or	
US-6204168-\$ or US-5824604-\$ or US-5798562-\$	1
or US-5445712-\$ or US-4431477-\$ or	
US-6225220-\$ or US-5114827-\$).did. or	
(US-20010005623-\$ or US-20020076935-\$).did.)	İ
and (DUV deep adj (UV ultra\$6))	
- 3 (((US-5877075-\$ or US-6149828-\$ or USPAT;	2003/12/29 12:08
US-6015597-\$ or US-6110826-\$ or US-6132631-\$ US-PGPUB	
or US-6080678-\$ or US-5911887-\$ or EPO; JPO	•
US-5910392-\$ or US-5779926-\$ or US-5721090-\$ DERWENT;	
or US-5397431-\$ or US-5362361-\$ or IBM TDB	
US-4793897-\$ or US-4615764-\$ or US-6444559-\$	
or US-6617257-\$ or US-6261905-\$ or	
US-6204168-\$ or US-5824604-\$ or US-5798562-\$	
or US-5445712-\$ or US-4431477-\$ or	
US-6225220-\$ or US-5114827-\$).did. or	
(US-20010005623-\$ or US-20020076935-\$).did.)	
and (DUV deep adj (UV ultra\$6))) and	I

-   3	((((US-5877075-\$ or US-6149828-\$ or	USPAT;	2003/12/29	12:02
	US-6015597-\$ or US-6110826-\$ or US-6132631-\$	US-PGPUB;		
·	or US-6080678-\$ or US-5911887-\$ or	EPO; JPO;		
	US-5910392-\$ or US-5779926-\$ or US-5721090-\$	DERWENT;		
	or US-5397431-\$ or US-5362361-\$ or	IBM_TDB		
	US-4793897-\$ or US-4615764-\$ or US-6444559-\$	_		
	or US-6617257-\$ or US-6261905-\$ or			
	US-6204168-\$ or US-5824604-\$ or US-5798562-\$			
i i	or US-5445712-\$ or US-4431477-\$ or			
	US-6225220-\$ or US-5114827-\$).did. or			
	(US-20010005623-\$ or US-20020076935-\$).did.)			
	and (DUV deep adj (UV ultra\$6))) and			
	(nitride sin si3n4 "si.sub.3 N.sub.4")) and			
	etch\$3 same (nitride sin si3n4 "si.sub.3			
	N. sub.4")	<u> </u>		